EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	958	(chemical near oxide) and ((monocrystal near silicon) (polycrystalline near silicon) (amorphous near silicon) (continous near grain near silicon) (silicon near carbide) and (silicon near germanium))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:19
L2	658	1 and @ad<="20050216"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:20
L3	37	2 and (chemical near oxide) with ((monocrystal near silicon) (polycrystalline near silicon) (amorphous near silicon) (continous near grain near silicon) (silicon near carbide) and (silicon near germanium))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:21
L4	10	(chemical near oxide) with contain$3 with ((monocrystal near silicon) (polycrystalline near silicon) (amorphous near silicon) (continous near grain near silicon) (silicon near carbide) and (silicon near germanium))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:32
L5	2669	438/197.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:36
L6	46	5 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:36

L7	1751	438/199.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:36
L8	19	7 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L9	1015	438/200.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L10	12	9 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L11	673	438/201.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L12	7	11 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L13	94	438/204.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L14	2	13 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37

L15	1098	257/e21.409.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:37
L16	18	15 and (chemical near oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:38
L17	113	257/e21.449.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/15 15:38
S1	31356	((silicon near oxynitride) (silicon near oxy-nitride) (sion)) and (cvd or ald or chemical near vapor near deposition or atomic near layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/23 10:42
S2	23	((((cvd) (chemical near vapor near deposition)) and ((silicon near oxynitride) (silicon near oxy-nitride) (sion)) and ((chlorosilane) (chlor$1 near3 silane) (dichlorosilane) (hexachlorosilane) (trichlorosilane)) and (oxidiz$3 oxygen) and (nitrid$3 nitrogen)).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/23 10:45
S5	3	S4 and (excitation near period) and (exciting near mechanism)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/23 10:50
S6	4	"6342133".pn. "4874493".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/05/02 19:15

6/15/2009 3:38:48 PM
C:\ Documents and Settings\ PDang1\ My Documents\ EAST\ Workspaces\ today021409.wsp